



RECEIVED
JUL 15 2003
TC 1700

Docket No. 50540

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: Brainard et al.

SERIAL NO.: 09/870,243

EXAMINER: S. Lee

FILED: May 30, 2001

GROUP: 1752

FOR: PHOTORESIST FOR IMAGING WITH HIGH ENERGY RADIATION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SIR:

AMENDMENT

Applicants are in receipt of the Office Action dated January 8, 2003. Please amend the above-identified application as follows.

IN THE CLAIMS

Please amend the following claims.

1. (twice amended) A method for forming a photoresist relief image on a substrate comprising:

(a) applying a coating layer of a chemically-amplified positive photoresist composition on a substrate, the photoresist composition comprising a resin and one or more photoacid generating compounds, wherein the one or more photoacid generator compounds are present in a concentration of at least 5 weight percent based on weight of total solids of the photoresist composition;

(b) exposing the photoresist coating layer to EUV radiation..

2. (twice amended) The method of claim 1 wherein the photoresist composition comprising a phenolic resin that comprises at least three distinct repeat units.